

ABSTRACT

INTERFEROMETRIC METHOD AND SYSTEM

The invention relates to an interferometric method for measuring a height of a first region on a first surface, the first surface having first areas having first optical properties and second areas having second optical properties, the method comprising the steps of generating of first and second coherent light beams, reflecting at least the first coherent light beam from the first region into a first return beam and reflecting the second coherent light beam from a second region into a second return beam, measuring at least a first reflectivity of the first region, determining a topography-dependent phase shift of the first and second return beams for the height measurement based on the first reflectivity.